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**AMENDMENTS TO THE CLAIMS:**

1. (Currently amended) A liquid crystal display device, comprising:  
a plurality of pixels arranged in a matrix form, each of said pixels comprising:  
a pixel electrode formation area wherein a pixel electrode is formed; and  
a thin film transistor formation area wherein a thin film transistor is formed  
and connected to said pixel electrode, said thin film transistor comprising:  
a semiconductor layer serving as a channel;  
a terminal formed to be connected to said pixel electrode;  
an inorganic insulating a passivation layer formed to cover said thin  
film transistor; and  
a transparent ~~an~~ organic insulating layer covering said passivation  
layer,  
wherein said pixel electrode formation area comprises a plurality of prism-shaped  
base posts, and an uneven layer formed on said plurality of prism-shaped base posts,  
wherein said semiconductor layer extends from said channel toward said pixel  
electrode formation area beyond said terminal and terminated in said pixel electrode  
formation area to form a termination end that is aligned with a termination end of said  
passivation layer, and  
wherein said organic insulating layer covers said termination ends of said  
semiconductor layer and said passivation layer.
2. (Original) The device as claimed in claim 1, wherein said pixel electrode is connected  
to said terminal of said thin film transistor through a contact hole that is selectively formed in  
said organic insulating layer and said passivation layer.
3. (Previously presented) The device as claimed in claim 1, wherein said uneven layer  
covers said plurality of prism-shaped base posts and is formed between said plurality of  
prism-shaped base posts.
4. (Previously presented) The device as claimed in claim 1, wherein said pixel electrode

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comprises a reflection-type electrode which is formed on said uneven layer.

5. (Currently amended) The device as claimed in claim 1, wherein said pixel electrode comprises a shape which follows a contour of said uneven layer.

6. (Previously presented) The device as claimed in claim 1, wherein said uneven layer comprises a transparent photosensitive resist.

7. (Previously presented) The device as claimed in claim 1, wherein said pixel electrode comprises one of sputtered aluminum and sputtered silver.

8. (Previously presented) The device as claimed in claim 1, further comprising:  
a transparent insulating substrate, said plurality of prism-shaped base posts being formed on said transparent insulating substrate.

9. (Previously presented) The device as claimed in claim 8, wherein said thin film transistor further comprises a gate insulation film formed on said transparent insulating substrate.

10. (Previously presented) The device as claimed in claim 9, wherein said plurality of prism-shaped base posts comprise:

an insulation film formed on said transparent substrate;  
a semiconductor film formed on said insulation layer; and  
an inorganic insulating film formed on said semiconductor layer.

11. (Currently amended) A liquid crystal display device, comprising:  
a plurality of pixels arranged in a matrix form, each of said pixels comprising:  
a pixel electrode formation area wherein a pixel electrode is formed; and  
a thin film transistor formation area wherein a thin film transistor is formed  
and connected to said pixel electrode, said thin film transistor comprising:  
a semiconductor layer serving as a channel;

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a terminal formed to be connected to said pixel electrode;  
a passivation layer formed to cover said thin film transistor; and  
an organic insulating layer covering said passivation layer,  
wherein said pixel electrode formation area comprises a plurality of prism-shaped  
base posts, and an uneven layer formed on said plurality of prism-shaped base posts,  
wherein said semiconductor layer extends from said channel toward said pixel  
electrode formation area beyond said terminal and terminated in said pixel electrode  
formation area to form a termination end that is aligned with a termination end of said  
passivation layer, and  
wherein said organic insulating layer covers said termination ends of said  
semiconductor layer and said passivation layer,  
wherein said device further comprises:  
a transparent insulating substrate, said plurality of prism-shaped base posts being  
formed on said transparent insulating substrate,  
wherein said thin film transistor further comprises a gate insulation film formed on  
said transparent insulating substrate,  
wherein said plurality of prism-shaped base posts comprise:  
an insulation film formed on said transparent substrate;  
a semiconductor film formed on said insulation layer; and  
an inorganic insulating film formed on said semiconductor layer, and  
The device as claimed in claim 10;  
wherein said insulation film, said semiconductor film, and said inorganic insulating  
film are formed concurrently with a formation of said gate insulation film, said  
semiconductor layer and said passivation film in said thin film transistor, respectively.

12. (Previously presented) The device as claimed in claim 1, wherein said thin film  
transistor further comprises a drain electrode, said pixel electrode being connected to said  
drain electrode via a contact through hole formed in said uneven layer, and a contact through  
hole passing through said passivation layer.

13. (Canceled)

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14. (Currently amended) A thin film transistor array substrate for a liquid crystal display device, said thin film transistor substrate comprising:

- an insulating substrate;
- a plurality of data lines formed on said insulating substrate;
- a plurality of gate lines formed on said insulating substrate, such that areas bounded by said plurality of gate lines and said plurality of data lines define a plurality of pixels in said liquid crystal display device;
- a plurality of thin film transistors respectively formed on said insulating substrate in said plurality of pixels;
- a plurality of prism-shaped base posts formed adjacent to a thin film transistor in each of said plurality of pixels;
- an uneven layer formed on said plurality of prism-shaped base posts, said uneven layer comprising a transparent organic insulating layer; and
- a pixel electrode formed on said uneven layer,

wherein said thin film transistor comprises:

- a gate insulation layer formed on said transparent insulating substrate;
- a semiconductor layer formed on said gate insulation layer; and
- an inorganic a passivation layer formed on said semiconductor layer.

15. (Previously presented) The device as claimed in claim 14, wherein said plurality of prism-shaped base posts comprises:

- an insulation film formed on said transparent substrate;
- a semiconductor film formed on said insulation layer; and
- an inorganic insulating film formed on said semiconductor layer.

16. (Currently amended) A thin film transistor array substrate for a liquid crystal display device, said thin film transistor substrate comprising:

- an insulating substrate;
- a plurality of data lines formed on said insulating substrate;
- a plurality of gate lines formed on said insulating substrate, such that areas bounded by said plurality of gate lines and said plurality of data lines define a plurality of pixels in said

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liquid crystal display device;

a plurality of thin film transistors respectively formed on said insulating substrate in said plurality of pixels;

a plurality of prism-shaped base posts formed adjacent to a thin film transistor in each of said plurality of pixels;

an uneven layer formed on said plurality of prism-shaped base posts; and

a pixel electrode formed on said uneven layer,

wherein said thin film transistor comprises:

a gate insulation layer formed on said transparent insulating substrate;

a semiconductor layer formed on said gate insulation layer; and

a passivation layer formed on said semiconductor layer,

wherein said plurality of prism-shaped base posts comprises:

an insulation film formed on said transparent substrate;

a semiconductor film formed on said insulation layer; and

an inorganic insulating film formed on said semiconductor layer, and

The device as claimed in claim 15,

wherein said insulation film, said semiconductor film, and said inorganic insulating film are formed concurrently with a formation of said gate insulation layer, said semiconductor layer and said passivation layer in said thin film transistor, respectively.

17. (Canceled)

18. (Currently amended) A method of forming a thin film transistor array substrate for a liquid crystal display device, comprising:

forming a plurality of data lines on a insulating substrate;

forming a plurality of gate lines on said insulating substrate, such that areas bounded by said plurality of gate lines and said plurality of data lines define a plurality of pixels in said liquid crystal display device;

forming a plurality of thin film transistors respectively on said insulating substrate in said plurality of pixels;

forming a plurality of prism-shaped base posts adjacent to a thin film transistor in

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each of said plurality of pixels;

forming an uneven layer comprising a transparent organic insulating layer on said plurality of prism-shaped base posts; and

forming a pixel electrode formed on said uneven layer,

wherein said forming said plurality of thin film transistors comprises:

forming a gate insulation layer on said transparent insulating substrate;

forming a semiconductor layer on said gate insulation layer; and

forming an inorganic insulating a passivation layer on said semiconductor layer.

19. (Previously presented) The device as claimed in claim 18, wherein said forming said plurality of prism-shaped base posts comprises:

forming an insulation film on said transparent substrate;

forming a semiconductor film on said insulation layer; and

forming an inorganic insulating film on said semiconductor layer.

20. (Currently amended) A method of forming a thin film transistor array substrate for a liquid crystal display device, comprising:

forming a plurality of data lines on a insulating substrate;

forming a plurality of gate lines on said insulating substrate, such that areas bounded by said plurality of gate lines and said plurality of data lines define a plurality of pixels in said liquid crystal display device;

forming a plurality of thin film transistors respectively on said insulating substrate in said plurality of pixels;

forming a plurality of prism-shaped base posts adjacent to a thin film transistor in each of said plurality of pixels;

forming an uneven layer on said plurality of prism-shaped base posts; and

forming a pixel electrode formed on said uneven layer,

wherein said forming said plurality of thin film transistors comprises:

forming a gate insulation layer on said transparent insulating substrate;

forming a semiconductor layer on said gate insulation layer; and

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forming a passivation layer on said semiconductor layer,  
wherein said forming said plurality of prism-shaped base posts comprises:  
forming an insulation film on said transparent substrate;  
forming a semiconductor film on said insulation layer; and  
forming an inorganic insulating film on said semiconductor layer, and

~~The device as claimed in claim 19;~~

wherein said forming said insulation film, forming said semiconductor film, and forming said inorganic insulating film are performed concurrently with said forming said gate insulation layer, forming said semiconductor layer and forming said passivation layer in said thin film transistor, respectively.

21. (New) The device as claimed in claim 1, wherein said organic insulating layer comprises a transparent acrylic resin.
22. (New) The device as claimed in claim 14, wherein said uneven layer comprises a transparent acrylic resin and covers said passivation layer.